

**Notice of References Cited**

Application/Control No.

09/809,766

Applicant(s)/Patent Under  
Reexamination  
FERRERA ET AL.

Examiner

Paul Gurzo

Art Unit

2881

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**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-4,393,312 ✓	07-1983	Collier et al.	250/492.2
	B	US-5,311,026 ✓	05-1994	Saitou et al.	250/492.23
	C	US-5,932,884 ✓	08-1999	Aizaki, Naoaki	250/492.2
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**NON-PATENT DOCUMENTS**

*		Included as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Goodberlet et al., "Extending Spatial-Phase-Locked Electron-Based Lithography to two Dimensions", Applied Physics, December 1997, pages 7557-7559.
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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.